

WEST**End f Result Set**

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L10: Entry 1 of 1

File: DWPI

Aug 10, 1999

DERWENT-ACC-NO: 1999-511248

DERWENT-WEEK: 199943

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TITLE: Crystallization of L-aspartic acid used as raw material
for chemicals, pharmaceuticals and food products, and as
chelating agent

PATENT-ASSIGNEE:

ASSIGNEE

MITSUBISHI CHEM CORP

CODE

MITU

PRIORITY-DATA:

1997JP-0322845

November 25, 1997

PATENT-FAMILY:

PUB-NO

PUB-DATE

LANGUAGE

PAGES

MAIN-IPC

JP 11217359 A

August 10, 1999

N/A

010

C07C227/42

APPLICATION-DATA:

PUB-NO

APPL-DESCRIPTOR

APPL-NO

APPL-NO

JP11217359A

November 24, 1998

1998JP-0332307

N/A

INT-CL (IPC): C07C 227/42; C07C 229/24

ABSTRACTED-PUB-NO: JP11217359A

BASIC-ABSTRACT:

NOVELTY - Crystallization of L-aspartic acid from its aqueous
solution is carried out in the presence of an acid deposition
agent. The degree of supersaturation (Delta pH) during
precipitation is maintained at 0.4 or less.

USE - Used as raw material for chemical, pharmaceutical and
food products, as chelating agent, surfactant and intermediate
for pharmaceutical and agro chemicals.

ADVANTAGE - L-aspartic acid of high purity is obtained with
sufficient reproducibility. Crystallization rate is effectively
controlled.

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: ASPARTIC ACID RAW MATERIAL CHEMICAL PHARMACEUTICAL
FOOD PRODUCT CHELATE AGENT

DERWENT-CLASS: B05 C03 D13 E16

CPI-CODES: B10-B02J; C10-B02J; D03-H01; E10-B02D5;

CHEMICAL-CODES:

Chemical Indexing M2 *01*

Fragmentation Code
H1 H100 H181 J0 J012 J1 J172 M280 M312 M321
M332 M343 M349 M381 M391 M416 M620 M720 M800 M903
M904 M910 N164 N421 Q220 Q504 Q616 R032
Specific Compounds
04095K 04095P
Registry Numbers
0114P

Chemical Indexing M3 *01*

Fragmentation Code
H1 H100 H181 J0 J012 J1 J172 M280 M312 M321
M332 M343 M349 M381 M391 M416 M620 M720 M800 M903
M904 M910 N164 N421 Q220 Q504 Q616 R032
Specific Compounds
04095K 04095P
Registry Numbers
0114P

UNLINKED-DERWENT-REGISTRY-NUMBERS: 0114P; 0901S ; 0902S

SECONDARY-ACC-NO:
CPI Secondary Accession Numbers: C1999-149789